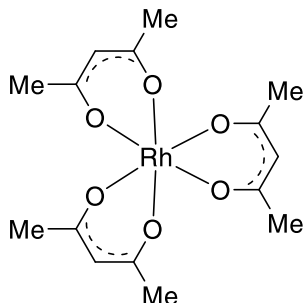


Catalog # 45-1800 Rhodium(III) acetylacetonate, 97+% (99.9%-Rh)



## Thermal Behavior:

- Melting point: 267°C [1]
- Decomposition at >280°C
- Sublimation at 240°C/0.1 Torr
- Vapor pressure: 0.02 Torr/150°C [2]

## Technical Notes:

1. ALD precursor for rhodium thin film deposition

Target Deposit	Deposition Technique	Delivery Temperature	Pressure	Co-reactants	Deposition Temperature	Ref.
Rh	ALD	150°C	8 Torr	O <sub>2</sub>	250°C	2
	ALD	150°C	7.5 Torr	O <sub>3</sub> , H <sub>2</sub>	200°C	3
	ALD	165°C	7.5 Torr	O <sub>3</sub>	200-220°C	4
Rh <sub>2</sub> O <sub>3</sub>	ALD	150°C	3.75-7.5 Torr	O <sub>3</sub>	160-200°C	5

## References:

1. [J. Electron. Mater. 1988, 17, 57](#)
2. [Electrochem. Solid-State Lett. 2005, 8, C99](#)
3. [Thin Solid Films 2013, 531, 243](#)
4. [RSC Adv. 2021, 11, 22773](#)
5. [J. Electrochem. Soc. 2009, 156, D418](#)